

<b>Notice of References Cited</b>	Application/Control No. 10/736,386		Applicant(s)/Patent Under Reexamination WHITEFIELD ET AL.	
	Examiner Hugh Jones		Art Unit 2128	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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*	B	US-2008/0021677	01-2008	Buxton et al.	702/184
*	C	US-6,847,855	01-2005	Poeppel, Gerhard	700/110
*	D	US-6,070,004	05-2000	Prein, Frank	716/10
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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Abercrombie et al. (inventors), Method for Calculating High-Resolution Wafer Parameter Profiles; 2004 IEEE/SEMI Advanced Semiconductor Manufacturing Conference, pp. 119-123.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.